

Claims

(1)

A manufacturing method of a display device, which uses droplet emitting means which uses a droplet emitting head in which a plurality of droplet emitting holes are disposed in a line form, and atmospheric pressure plasma processing means which uses plasma generating means under atmospheric pressure or vicinity of atmospheric pressure, and

the manufacturing method of a display device characterized by forming a pattern which comprises a composition which is emitted by use of the droplet emitting means, and to carry out plasma processing to the pattern by use of the plasma processing means.

(2)

A manufacturing method of a display device, which uses droplet emitting means which uses a droplet emitting head in which a plurality of droplet emitting holes are disposed in a line form, and atmospheric pressure plasma processing means which uses plasma generating means under atmospheric pressure or the vicinity of atmospheric pressure, and

the manufacturing method of a display device characterized by carrying out formation of resist and wiring by use of the droplet emitting means, and by carrying out ashing of the resist and etching of the wiring by use of the plasma

processing means.

(3)

A manufacturing method of a display device, which uses droplet emitting means which uses a droplet emitting head in which a plurality of droplet emitting holes are disposed in a line form, and atmospheric pressure plasma processing means which uses plasma generating means under atmospheric pressure or the vicinity of atmospheric pressure, and

the manufacturing method of a display device characterized by carrying out formation of resist by use of the droplet emitting means, and by carrying out ashing of the resist and etching of an electric conductive film which is disposed under the resist by use of the plasma processing means.

(4)

A manufacturing method of a display device, which uses droplet emitting means which uses a droplet emitting head in which one or a plurality of droplet emitting holes are disposed, and plasma processing means for carrying out local plasma processing which has plasma generating means under atmospheric pressure or the vicinity of atmospheric pressure, and

the manufacturing method of a display device, characterized by forming a pattern which comprises a composition which is emitted by use of the droplet emitting means, and by carrying out plasma processing to the pattern by use of the plasma processing means.

(5)

A manufacturing method of a display device, which uses droplet emitting means which uses a droplet emitting head in which one or a plurality of droplet emitting holes are disposed, and plasma processing means for carrying out local plasma processing which has plasma generating means under atmospheric pressure or the vicinity of atmospheric pressure, and

the manufacturing method of a display device, characterized by carrying out formation of resist and wiring by use of the droplet emitting means, and by carrying out ashing of the resist and etching of the wiring by use of the plasma processing means.

(6)

A manufacturing method of a display device, which uses droplet emitting means which uses a droplet emitting head in which one or a plurality of droplet emitting holes are disposed, and plasma processing means for carrying out local plasma processing which has plasma generating means under atmospheric pressure or the vicinity of atmospheric pressure, and

the manufacturing method of a display device, characterized by carrying out formation of resist by use of the droplet emitting means, and by carrying out ashing of the resist and etching of wiring by use of the plasma processing means.

(7)

A manufacturing method of a display device characterized in that, as the droplet in claims 1 through 6, used is any one of a photosensitive resist, a paste form metal material or organic liquid solution which includes the paste form metal, a ultra-fine particle form metal material or organic liquid solution which includes the metal material.

(8)

A manufacturing method of a display device, which uses atmospheric pressure plasma processing means which uses plasma generating means under atmospheric pressure or the vicinity of atmospheric pressure, and

the manufacturing method of a display device, characterized by forming wiring, by carrying out etching an electric conductive film, which is formed on a substrate to be processed, by use of the plasma processing means.

(9)

A manufacturing method of a display device, which uses plasma processing means which has plasma generating means under atmospheric pressure or the vicinity of atmospheric pressure, for carrying out local plasma processing, and

the manufacturing method of a display device, characterized by forming wiring, by carrying out etching an electric conductive film, which is formed on a substrate to be processed, by use of the plasma processing means.

(10)

A manufacturing method of a display device, which uses droplet emitting means which uses a droplet emitting head in which a plurality of droplet emitting holes are disposed in a line form, and

the manufacturing method of a display device characterized by forming a groove part in an insulating film which is formed on a glass substrate, emitting a composition in the groove, by use of the droplet emitting means, and forming a pattern which comprises the composition along the groove, thereby it being used as a wiring.

(11)

A manufacturing method of a display device, which uses droplet emitting means which uses a droplet emitting head in which one or a plurality of droplet emitting holes are disposed in a line form, and

the manufacturing method of a display device characterized by forming a groove part in an insulating film which was formed on a glass substrate, and emitting a composition in the groove, by use of the droplet emitting means, and forming a pattern which comprises the composition along the groove, to thereby form a wiring.

(12)

A display device having a glass substrate, a first thin film which is formed on the glass substrate, a pattern which comprises a composition which is emitted on the first thin film,

and a second thin film which is formed on the pattern, and
a manufacturing method of the display device
characterized in that the pattern is emitted by droplet emitting
means which uses a droplet emitting head in which a plurality
of droplet emitting holes are disposed in a line form, and formed
in a matrix form.

(13)

A display device having a glass substrate, a first thin
film which is formed on the glass substrate, a pattern which
comprises a composition which is emitted on the first thin film,
and a second thin film which is formed on the pattern, and

a manufacturing method of the display device
characterized in that the pattern is emitted by droplet emitting
means which uses a droplet emitting head in which one or a
plurality of droplet emitting holes are disposed in a line form,
and formed in a matrix form.

(14)

A manufacturing method of a display device, including
a process of emitting an electric conductive film, which
becomes a wiring, on a substrate, by use of droplet emitting
means,

a process of forming a resist pattern by emitting a resist
on the electric conductive film by use of the droplet emitting
means,

a process of carrying out etching of the electric

conductive film with the resist pattern as a mask, by use of plasma processing means, and

a process of carrying out ashing of the resist pattern by use of the plasma processing means, to form a wiring, and

the manufacturing method of a display device characterized in that the droplet emitting means is equipped with a droplet emitting head in which a plurality of droplet emitting holes are disposed in a line form, and

the plasma processing means is equipped with plasma generating means under atmospheric pressure or the vicinity of atmospheric pressure.

(15)

A manufacturing method of a display device, including a process of emitting an electric conductive film, which becomes a wiring, on a substrate, by use of droplet emitting means,

a process of forming a resist pattern by emitting a resist on the electric conductive film by use of the droplet emitting means,

a process of carrying out etching of the electric conductive film with the resist pattern as a mask, by use of plasma processing means, and

a process of carrying out ashing of the resist pattern by use of the plasma processing means, to form a wiring, and

the manufacturing method of a display device

characterized in that the droplet emitting means is equipped with a droplet emitting head in which one or a plurality of droplet emitting holes are disposed in a line form, and

the plasma processing means has plasma generating means under atmospheric pressure or the vicinity of atmospheric pressure for carrying out local plasma processing.

(16)

A manufacturing method of a display device characterized in that, as the droplet in claims 8 through 15, used is any one of a photosensitive resist, a paste form metal material or organic liquid solution which includes the paste form metal, a ultra-fine particle form metal material or organic liquid solution which includes the metal material.